

ABSTRACT OF THE DISCLOSURE

5 A photolithography apparatus includes: an air supply line supplying
an air to a chamber processing a wafer; a temperature and humidity
adjuster provided to the air supply line; a temperature and humidity
10 monitoring sensor sensing temperature and humidity internal to the
chamber; and a controller connected to the temperature and humidity
monitoring sensor and the temperature and humidity adjuster to control the
temperature and humidity adjuster to supply the chamber via the air supply
line with an air having the same temperature and humidity as those of the
10 air in the chamber detected by the temperature and humidity monitoring
sensor.